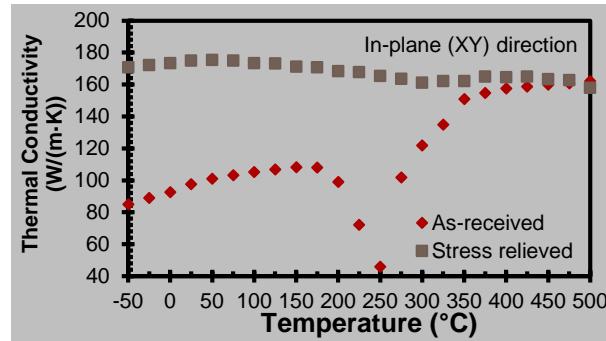
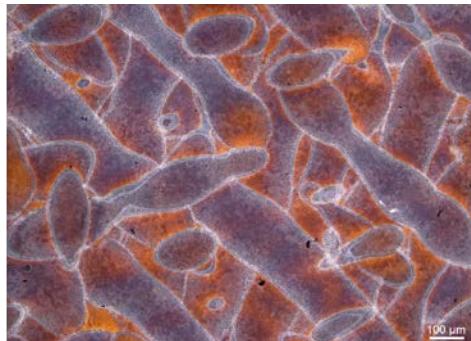


Exceptional service in the national interest



The Change of Thermal Properties and Microstructure of an AM Fabricated AlSi10Mg Alloy During Thermal Annealing

Pin Yang*, Mark A. Rodriguez, Daniel K. Stefan, Amy Allen, Donald Bradley, Lisa Deibler, and H. Jared

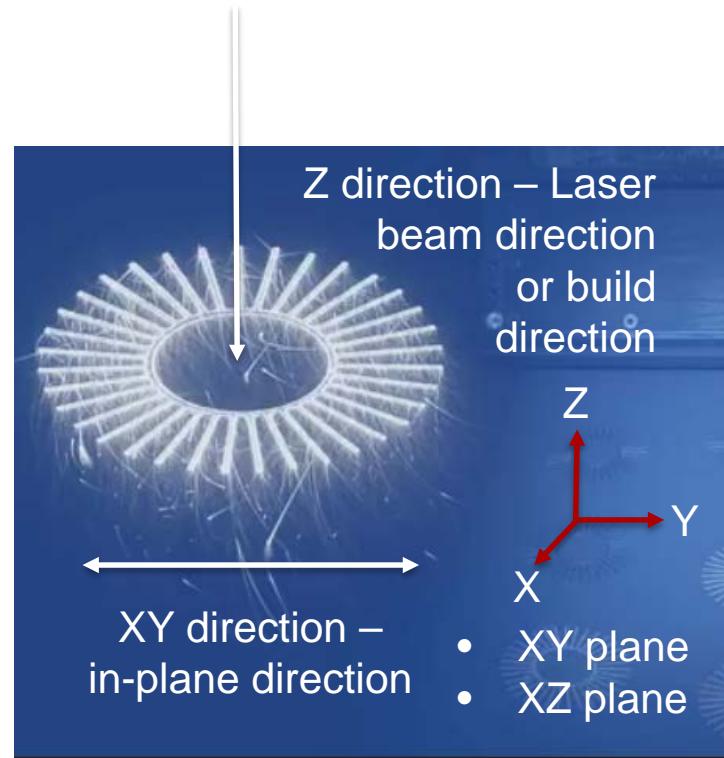


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AM – Selective laser melting process

Advantages of Laser-based AM Process:

- Agility and flexibility in design/fabrication of intricate components
- Quick turn-around time for manufacturing and critical in-mission repair
- Conservation of source materials
- Reduction in manufacturing footprint and ancillary tooling requirement
- Unique physical properties: non-equilibrium state
 - Superior high hardness†
 - High strength and cycle fatigue resistance*



Modified from Edelstahl Rosswag Engineering

† A. Martens et al., 26th SSF symposium , 1007-1016 (2005)

*E. Brandl et al., *Mater Des*, **34** 159-169 (2012) and

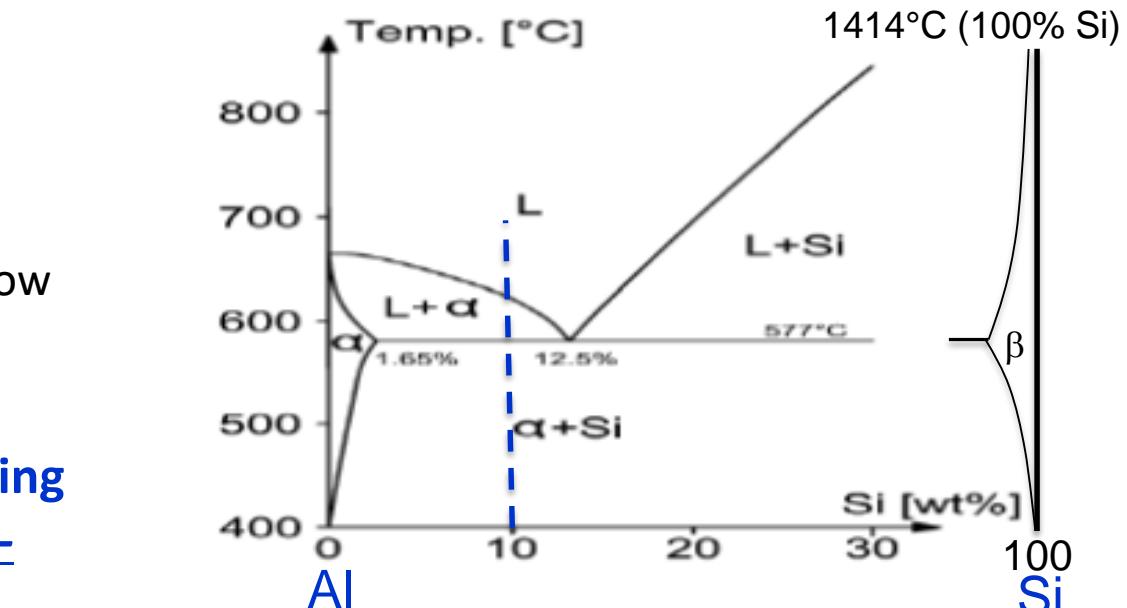
AlSi10Mg – Light weight, good strength, hardness, as well as dynamic and thermal properties

- Phase diagram - AlSi10Mg:
 - Hypoeutectic composition
 - Lower melting point
 - Narrow solidification window

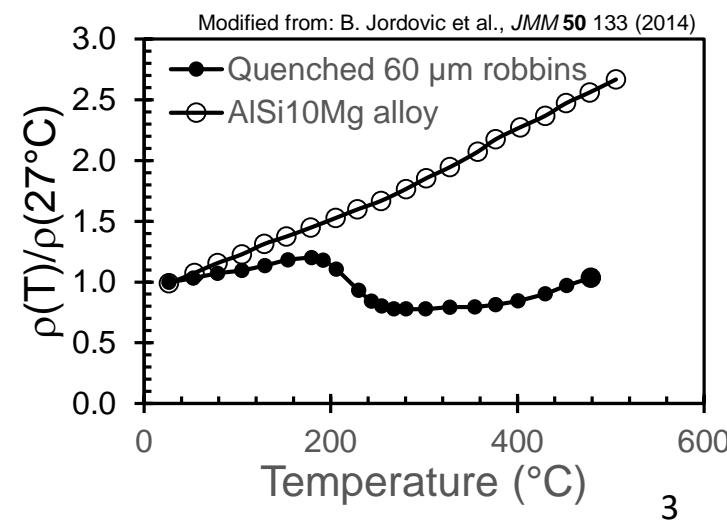
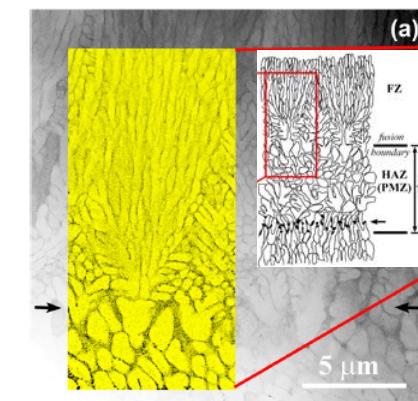
Automobile, aerospace, structural and thermal applications

Rapid melting and fast quenching in AM process introduce a non-equilibrium state

- Ultrafine, textured, devoiced eutectic cellular microstructure
- Increased Si solubility in Al
- Residual stresses
- High concentration of lattice defects and low thermo-electromotive force



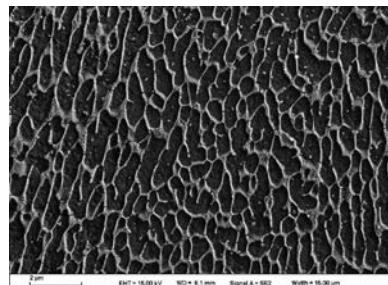
Modified from: Holesinger et al., *JOM* **68** 1000 (2016). Cellular wall has high concentration of Si and Mg.



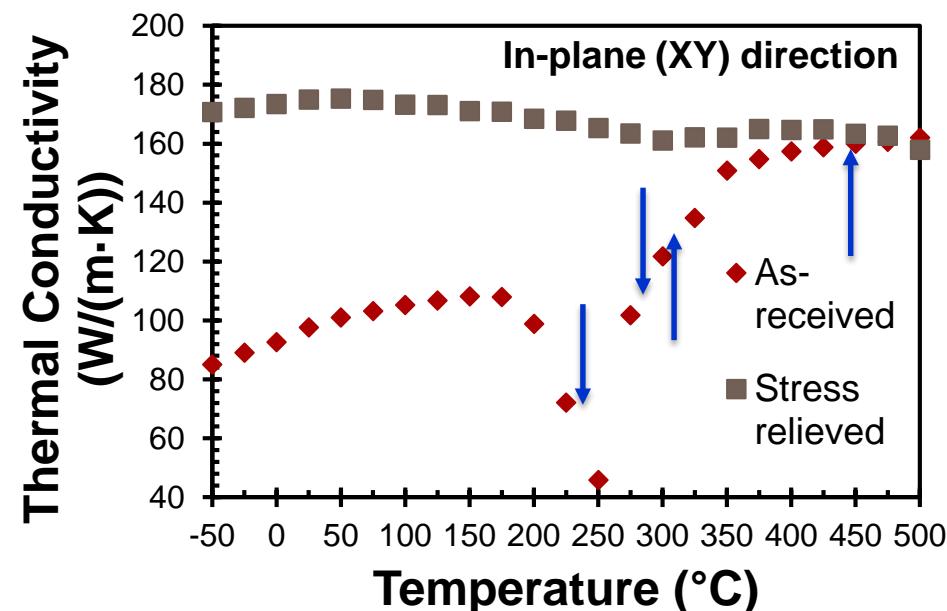
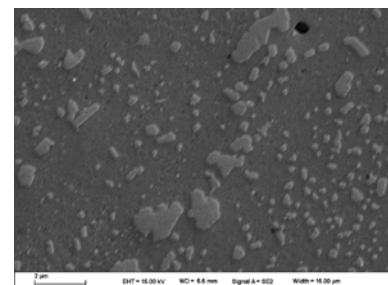
Objectives

- Compare microstructure and thermal properties of as-built and thermally annealed AM fabricated parts to highlight the differences imparted by a non-equilibrium process
- Correlate the microstructure evolution and thermal properties and compare with a first order calculation to shed light on thermophysical changes in AM fabricated AlSi10Mg parts

As-built



Thermally annealed



Things which affect heat transfer

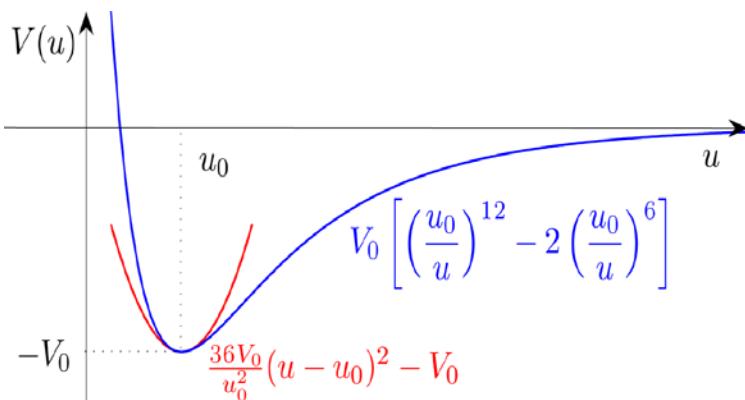
Phonon gas and collisions



$$\text{Conservation of momentum: } K_1 + K_2 = K_3 + G$$

- $G = 0$: Normal processes – no collision
- $G \neq 0$: Umklapp processes – collision and scattering

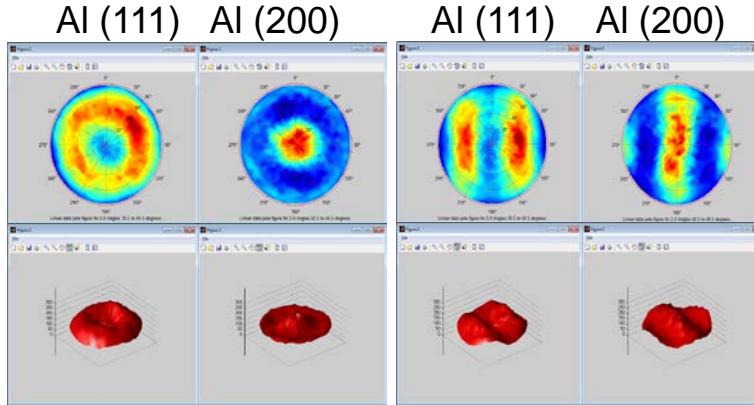
- Anharmonicity vibration in lattice and scattering



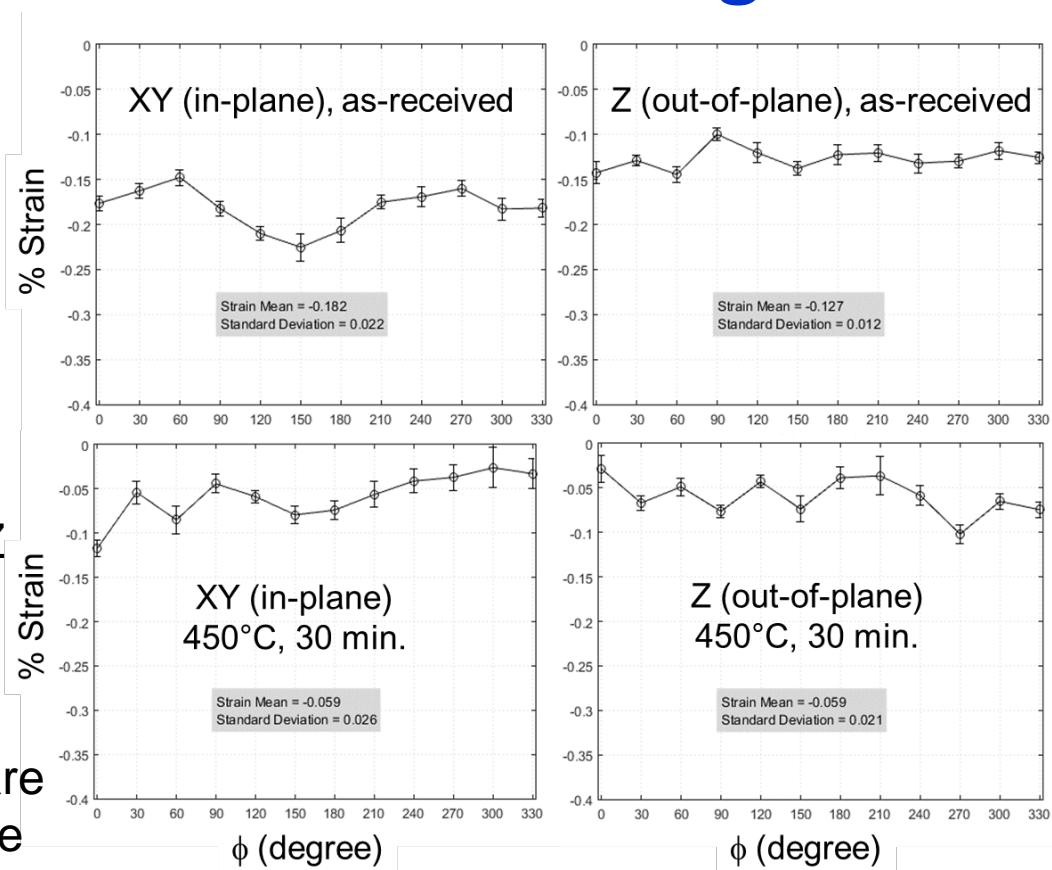
Things can affect electron and phonon scattering:

- (1) Bulk – contact interfaces, residual stresses
- (2) Microstructure – boundaries (FZ, grain, cellular), porosity
- (3) Atomic level – lattice defects, foreign atoms (alloying), dislocations, ...
- (4) Soft phonon modes, ... , etc.

Bulk - Residual stress induced scattering

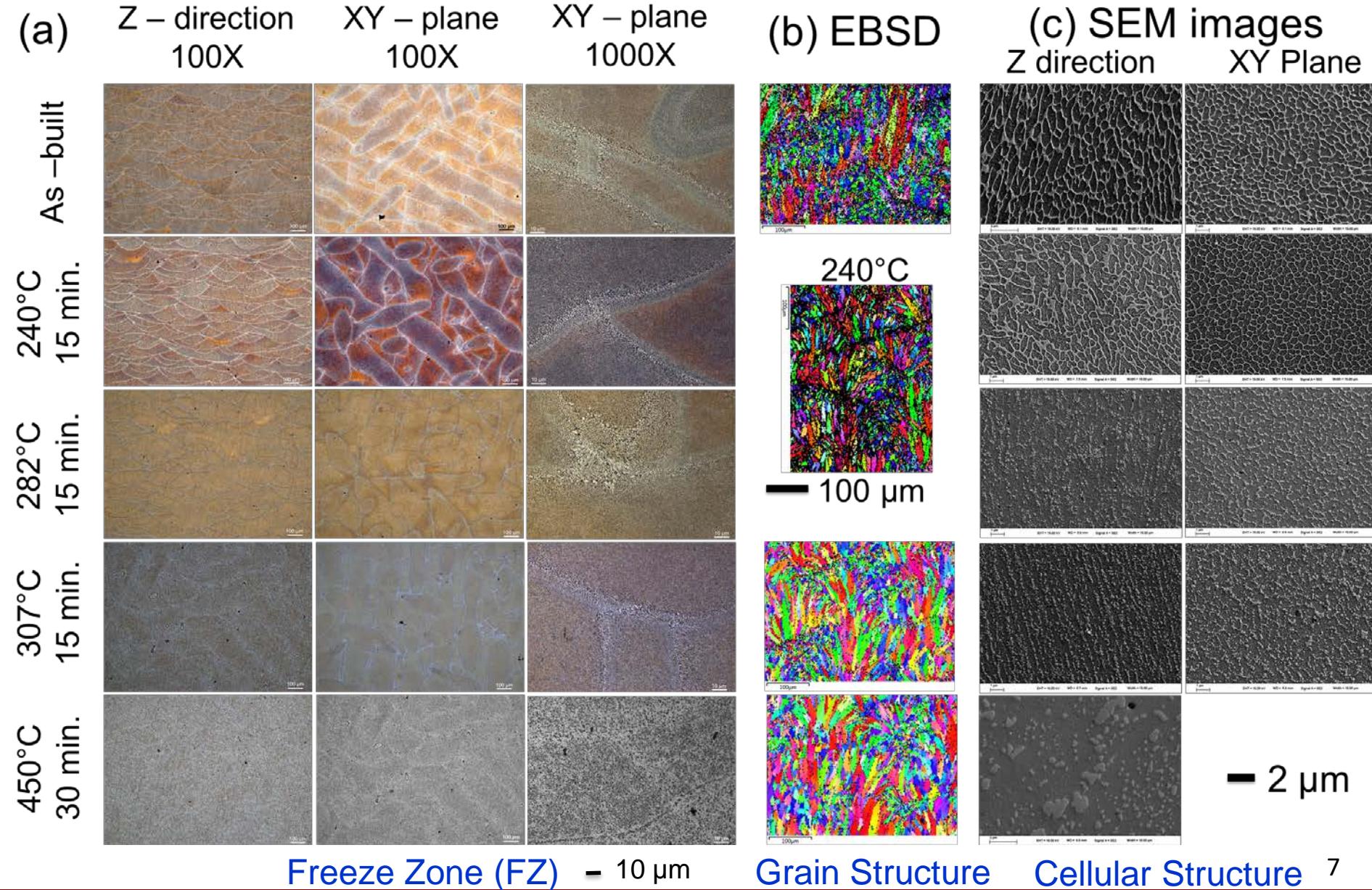


- XY samples have a typical (200) out of plane orientation, while the Z samples show a (200) rolling texture.
- The compressive in-plane strains presented in the as-built samples are initially significant, with values in the -0.18% for the XY samples and -0.13 to -0.17% for the Z samples. Heat treatment significantly decreases residual strain values down to about -0.06% for both the XY and X samples.

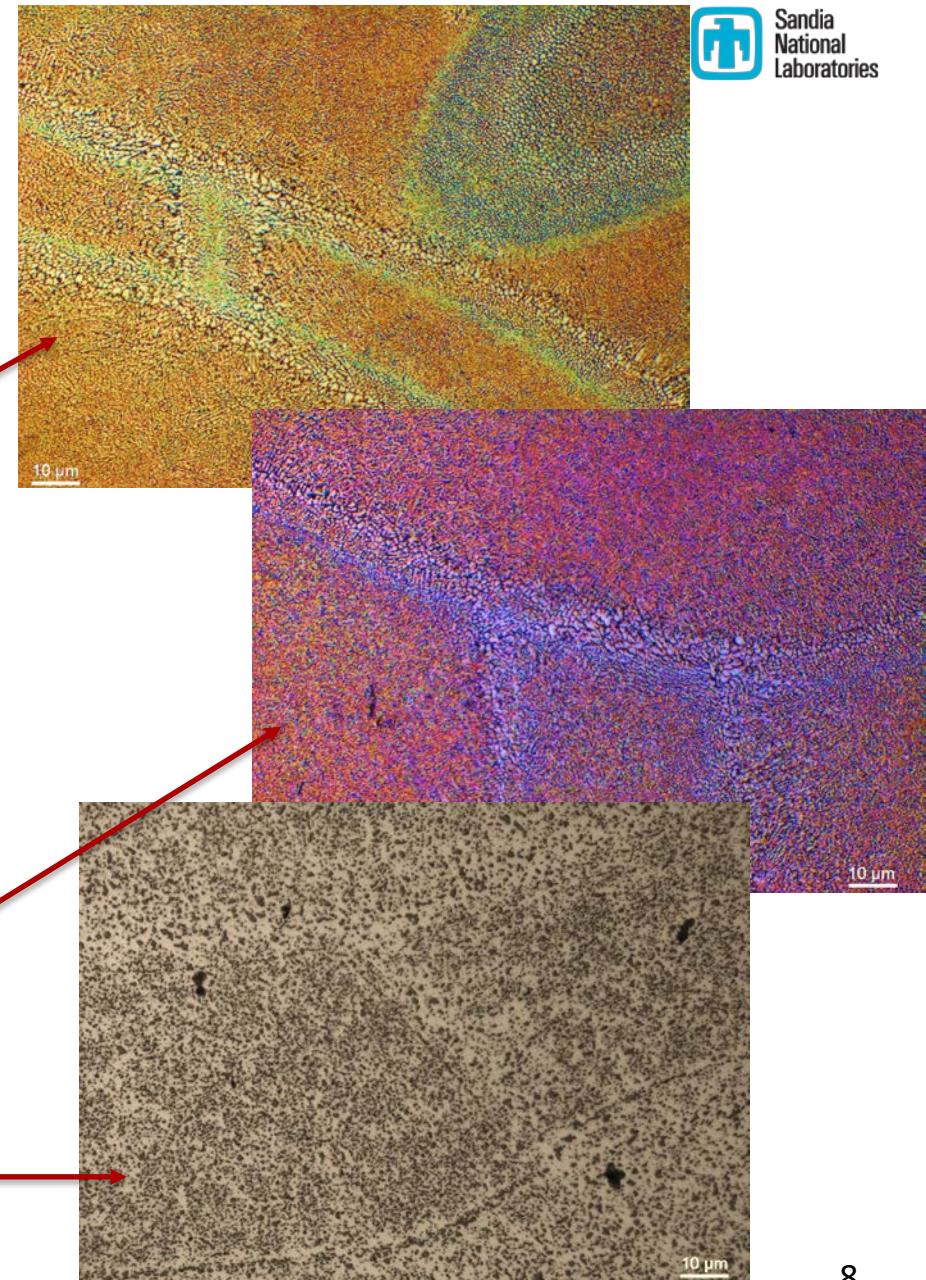
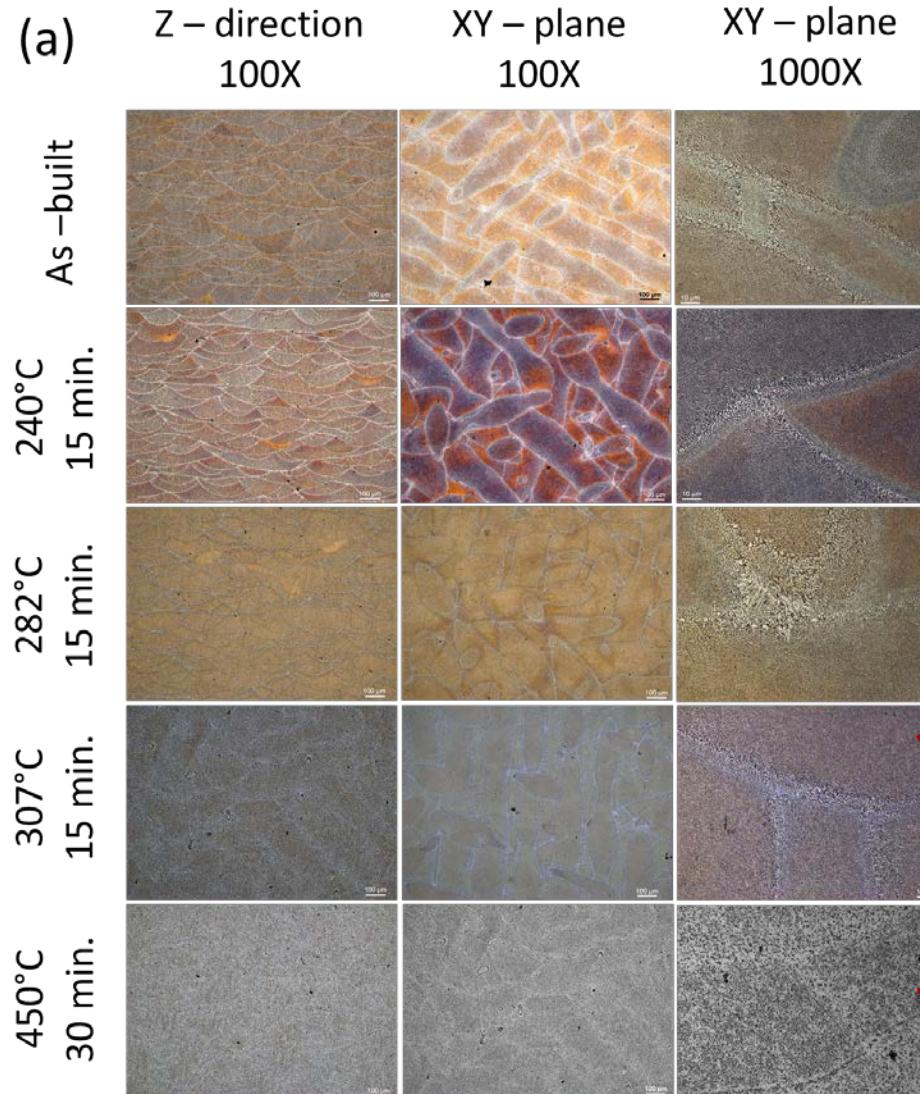


- AM process introduces crystalline texture and an “isotropic” compressive stress in the part during rapid solidification.
- An “isotropic residual stress state” should not significantly affect the heat transfer.

Microstructure and Temperature

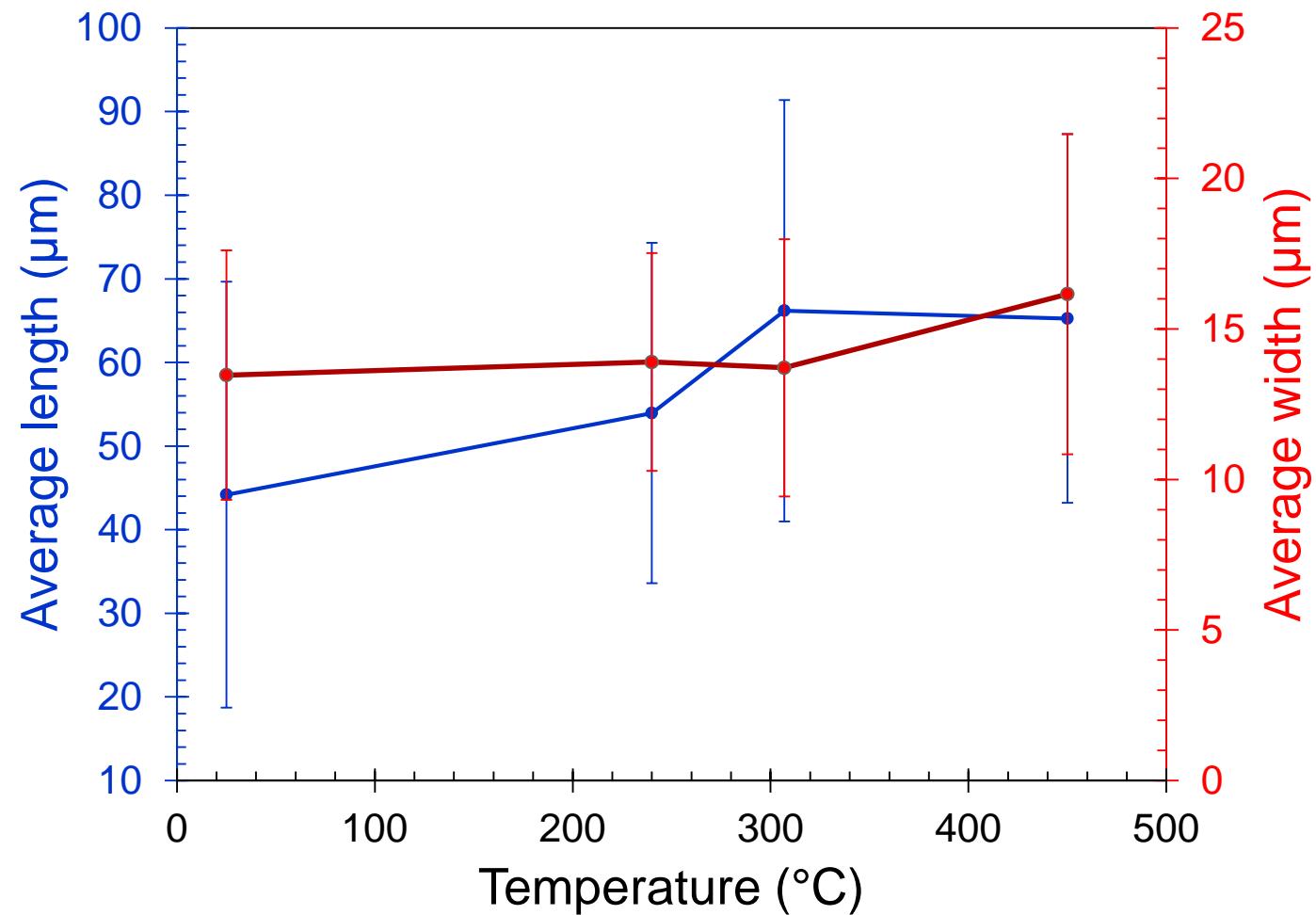
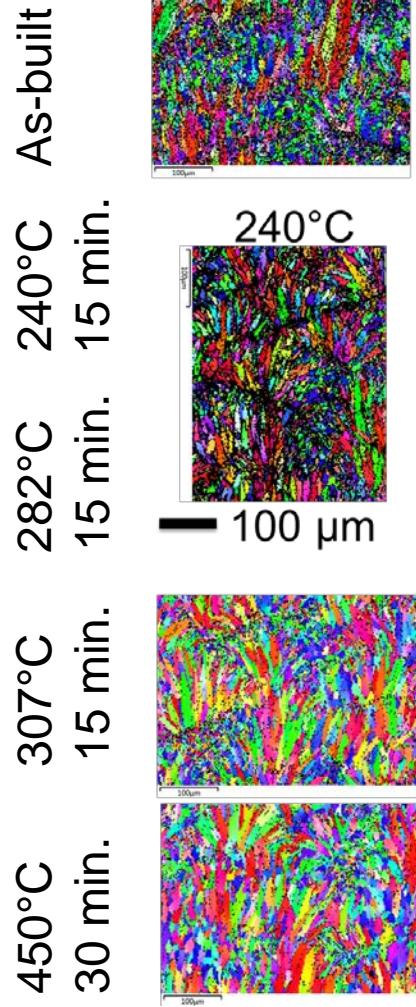


Microstructure change of freeze zone boundary

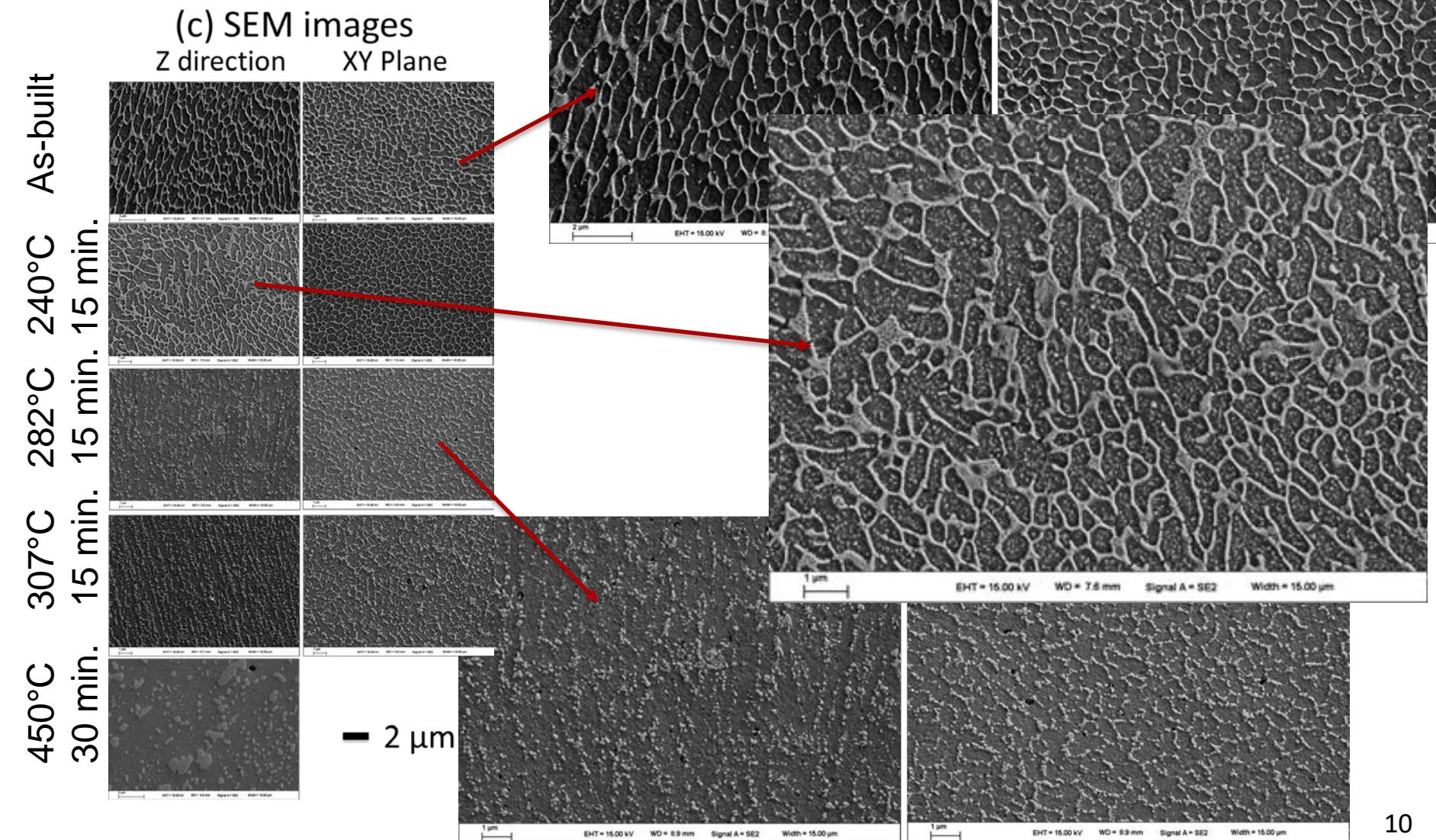


Change in grain size

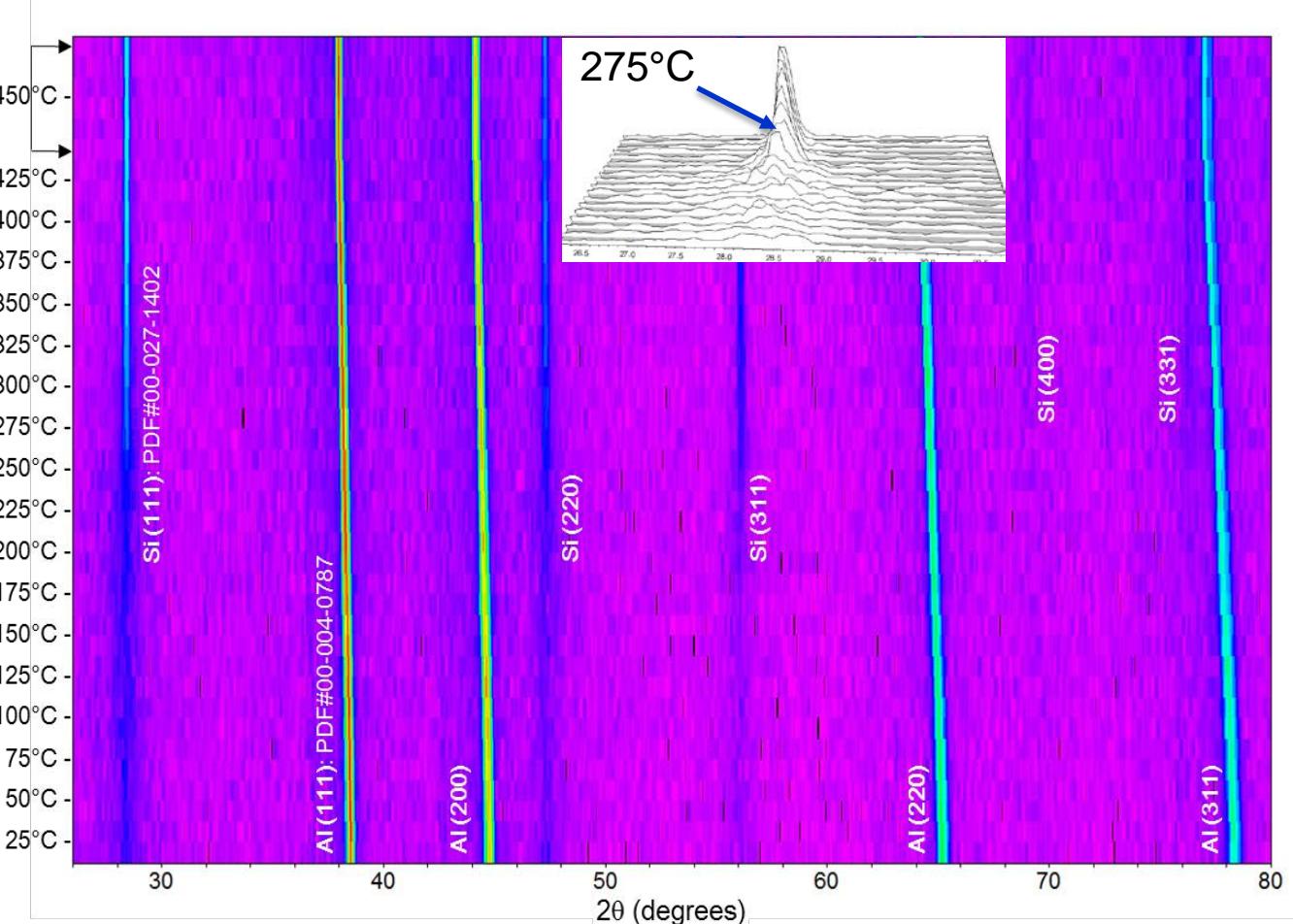
(b) EBSD



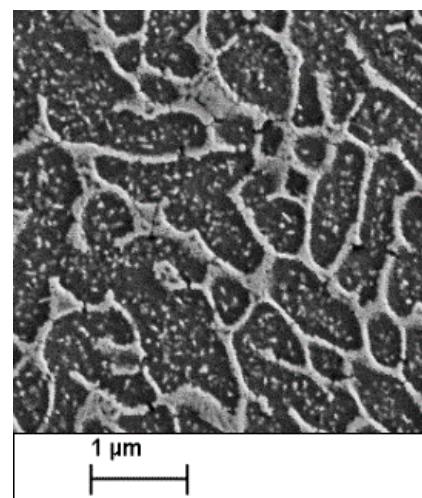
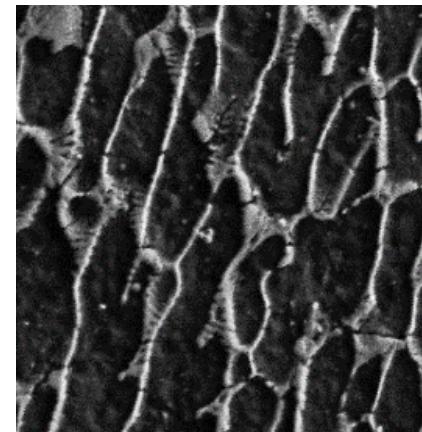
Microstructure evolution of cellular structure



Dissolution of silicon



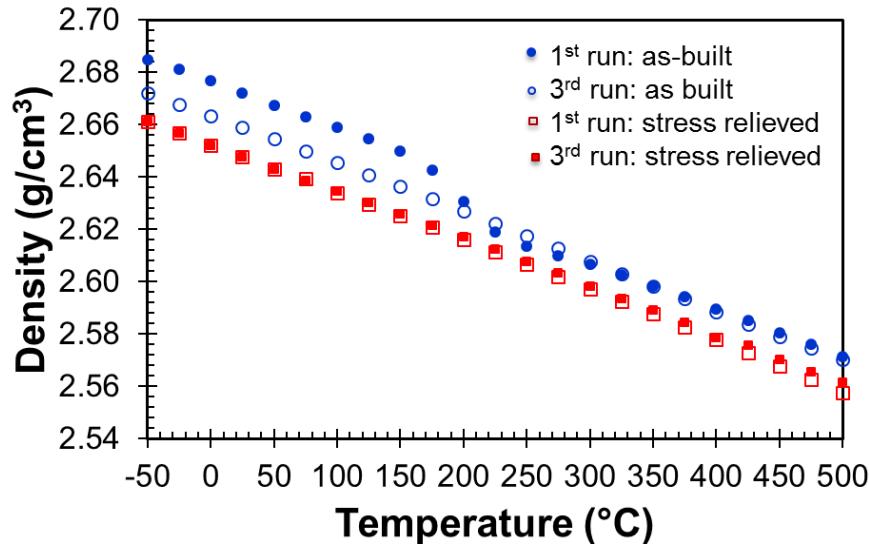
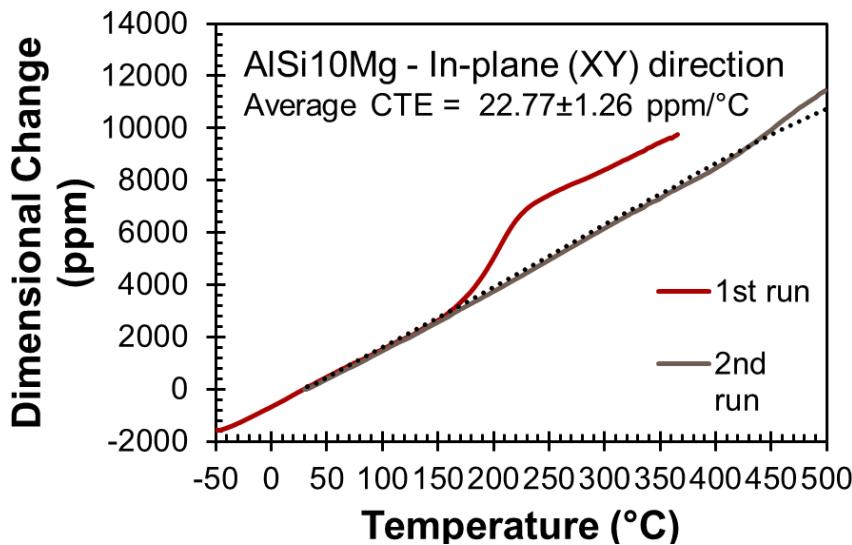
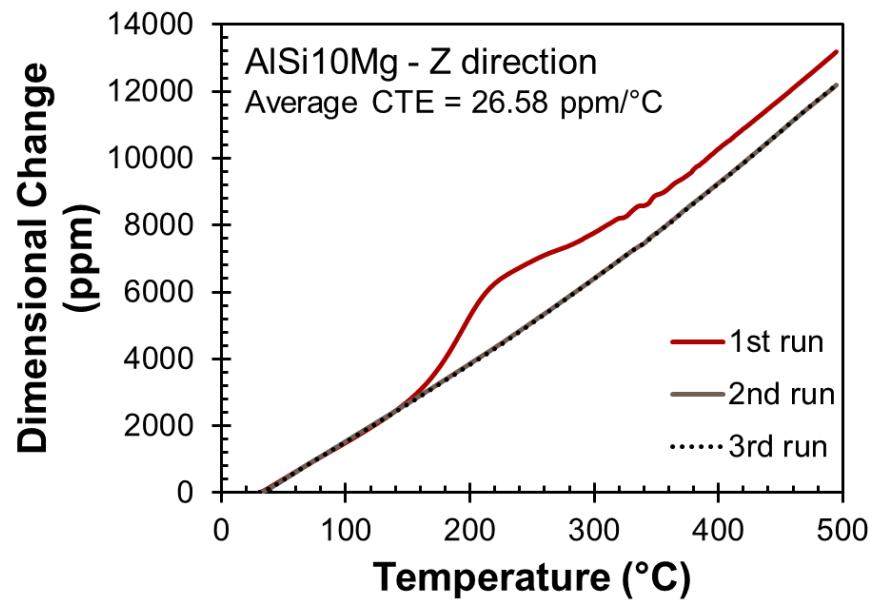
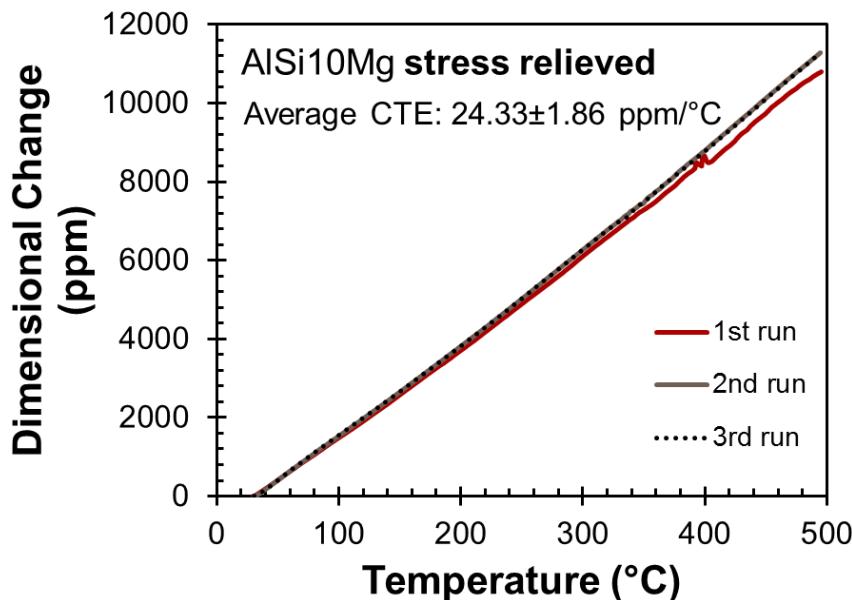
As-built



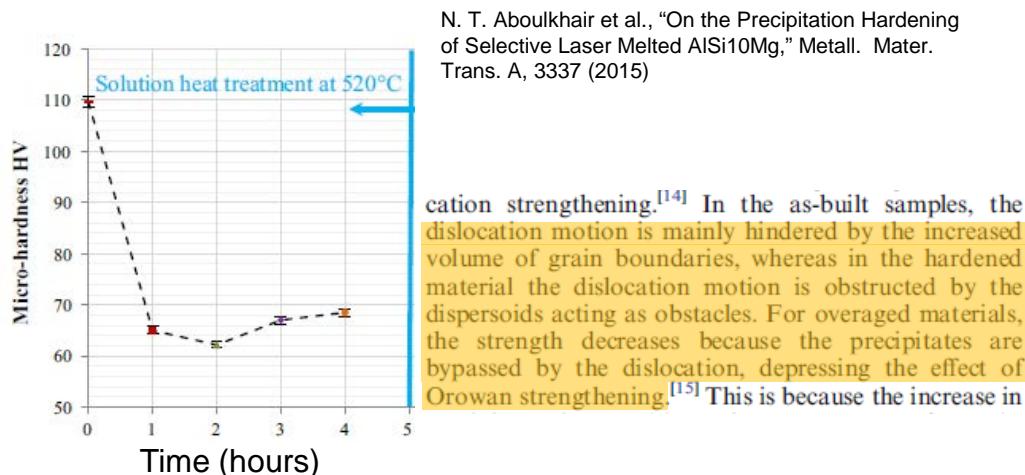
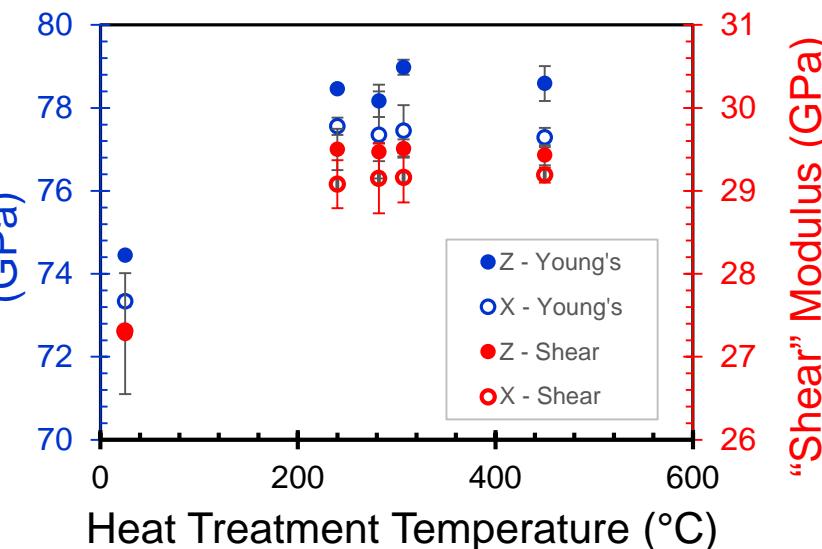
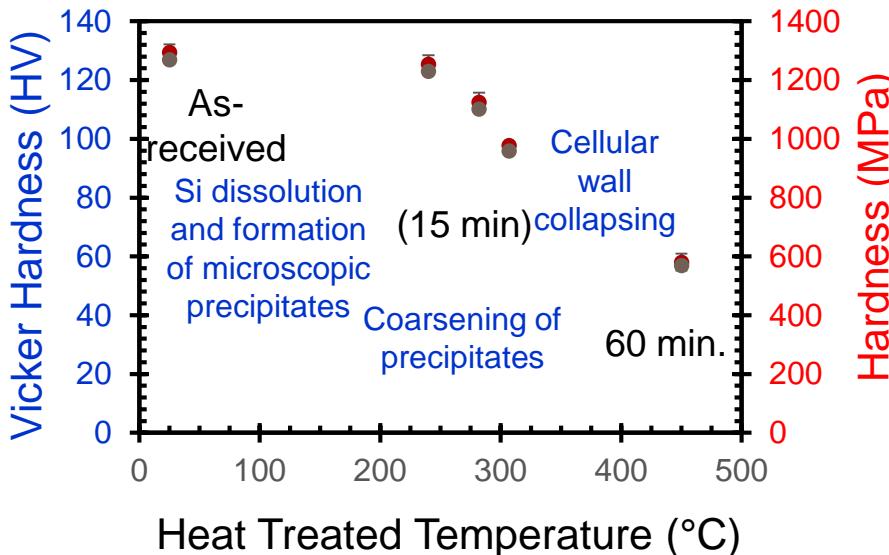
240°C, 15 min.

- Below 150°C, excess Si forms nano-clusters in the alloy.
- Coarsening of Si nanoclusters is observed above 240°C.

Thermomechanical response and density (ρ)

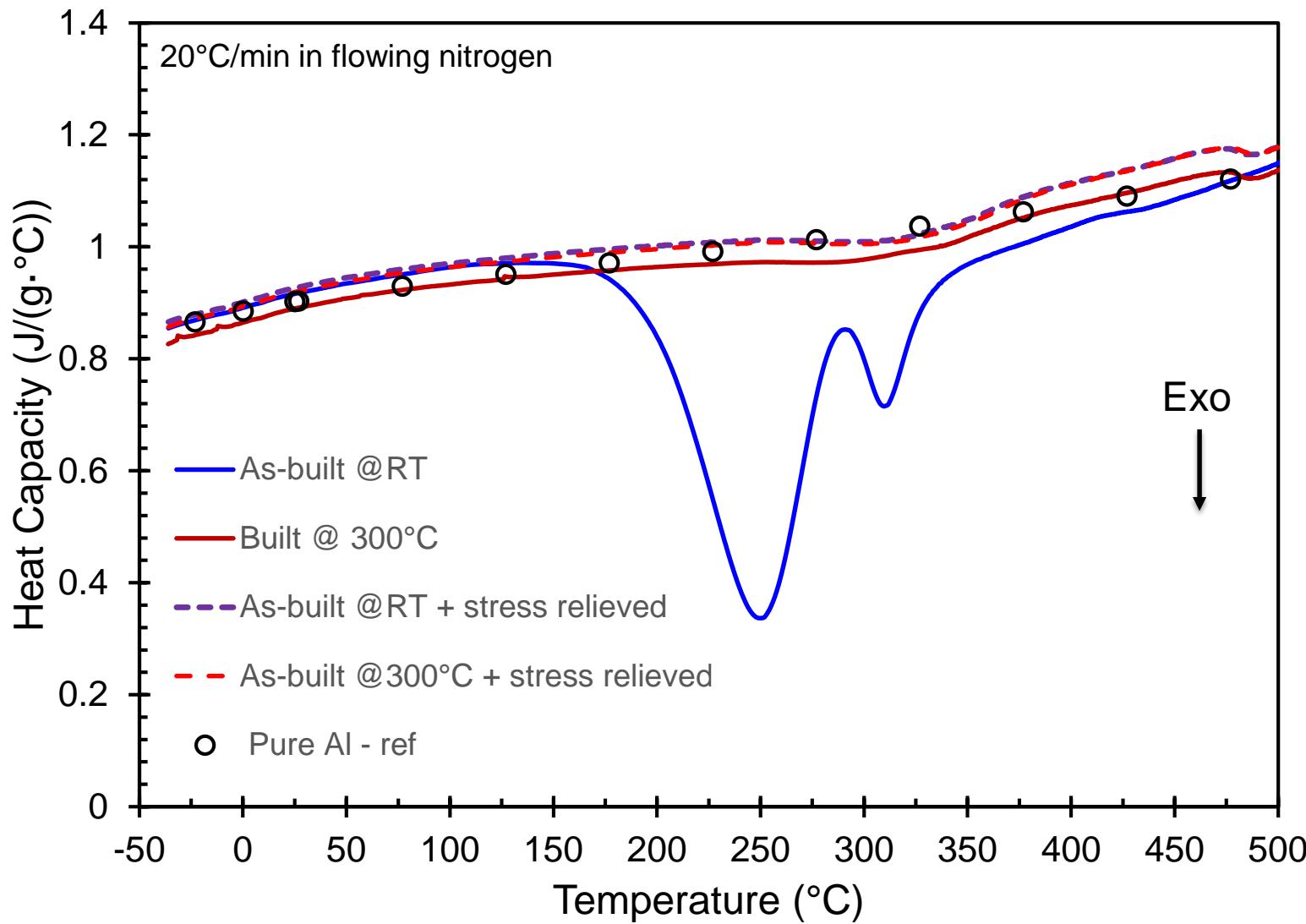


Hardness and Elastic Constants



- Hardness in the as-built part is dominated by the “nano-cluster” hardening and solution hardening.
- Microhardness progressively decreases as the dominant mechanism changes from solution hardening to precipitation hardening, to collapsing of cellular wall, and spheroidizing.

Heat capacity as a function of temperature



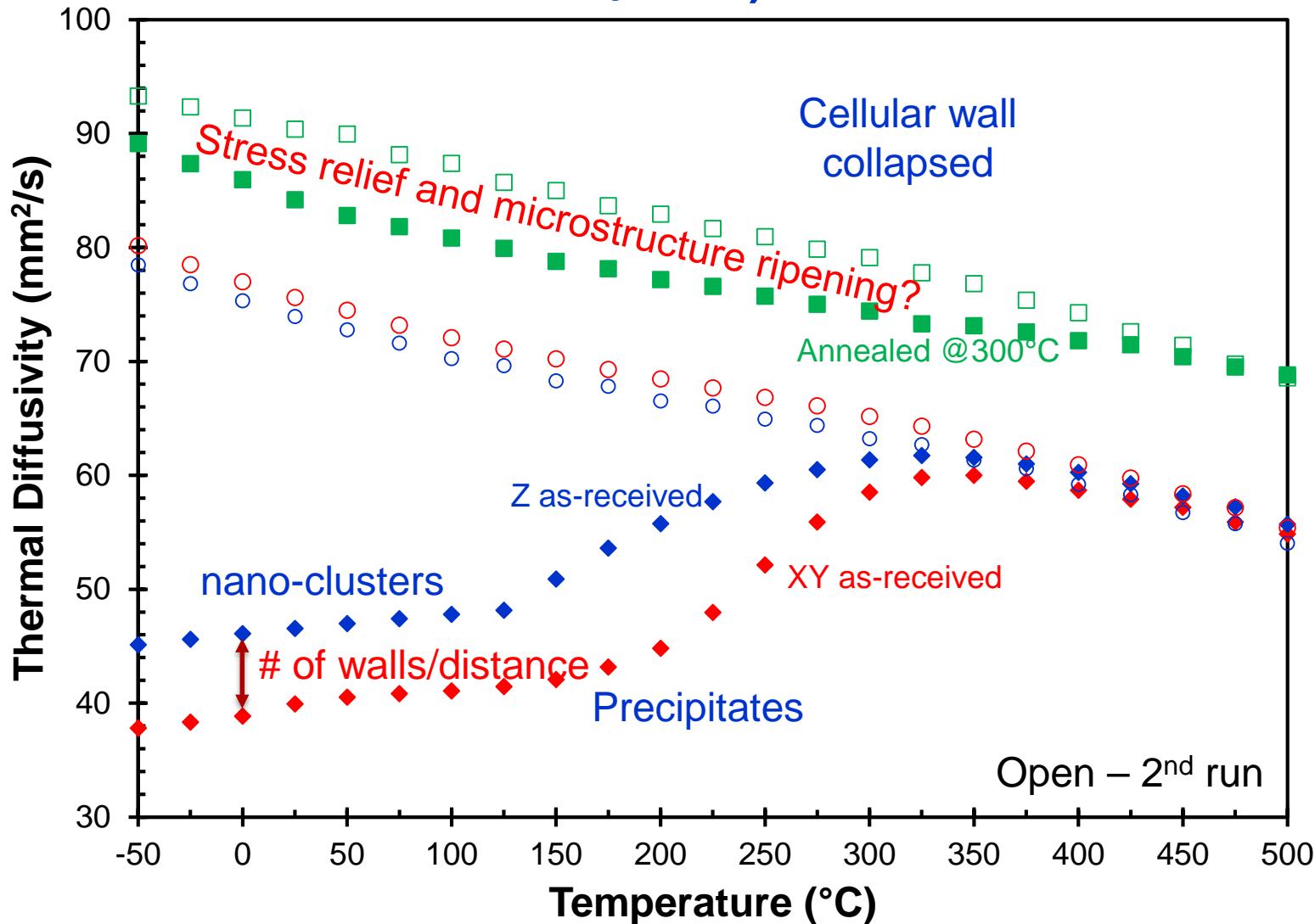
1st order calculation of thermal properties

Room Temperature Properties for Aluminum and Al Si10Mg Alloy from Literature* and Calculation.

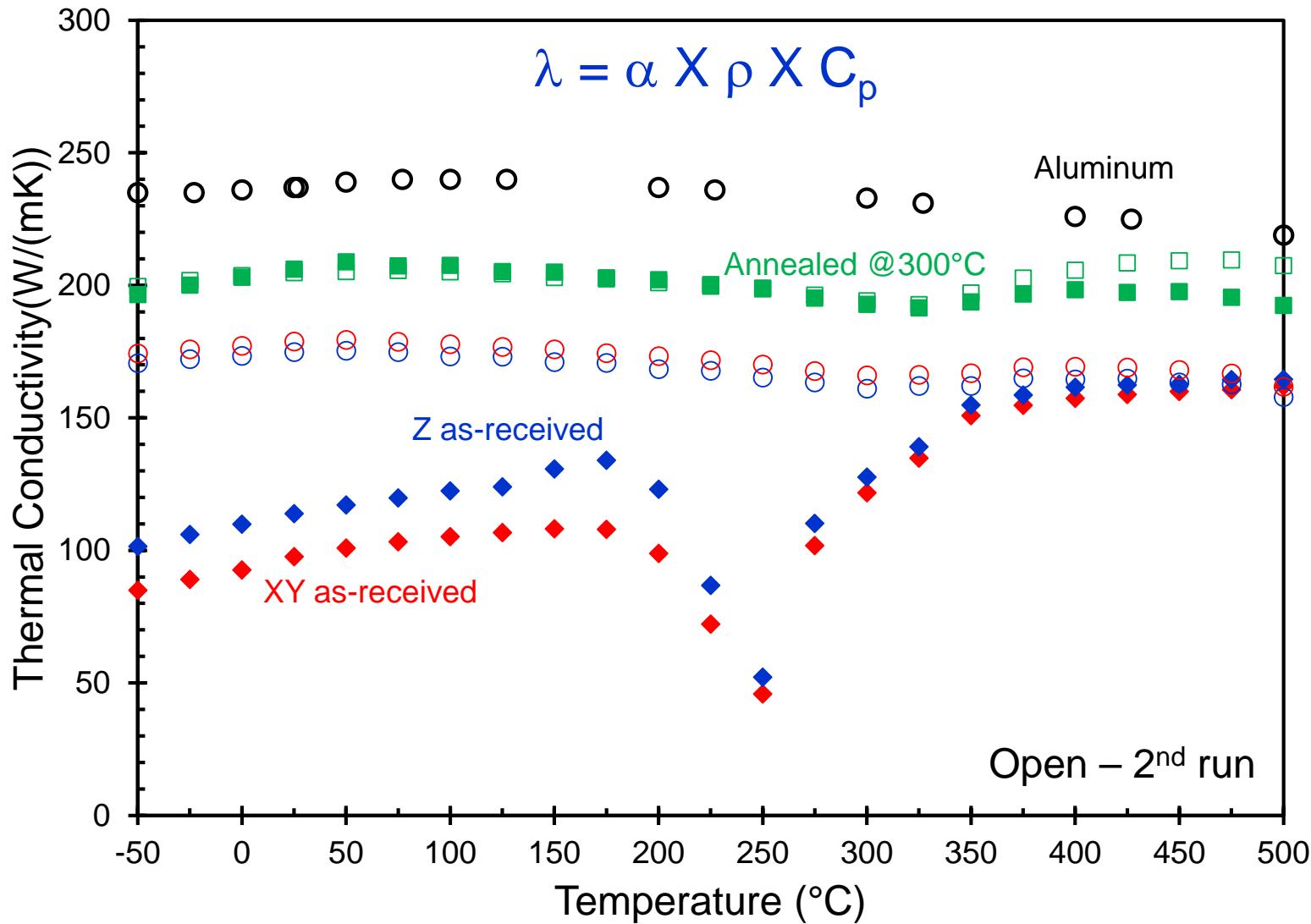
Electronic Contribution to Thermal Properties			Reference
Al	Free electronic density – (e/m ³)	1.809 X10 ²⁹	REF * Depends on XY or Z plane † At 240°C, before wall collapsed
	Fermi Level (E_F) at 0 K – (eV)	11.66	
	Electron velocity at Fermi Level (V_F) – (m/s)	2024917	
	Time between collision (τ) – (s)	7.16 X 10 ⁻¹⁵	
	Electron mean-free-path (l_e) – (Å)	145.1	
	Electrical conductivity* (σ) – (Ohm ⁻¹ cm ⁻¹)	365 X10 ³	
	Calculated thermal conductivity (σ) – (W/m·K)	267.7	
Thermal conductivity* (λ_e) – (W/m·K)			NIST
			Average size and distance
			FZ boundary >> or > 100 μm
			Grain boundary 15 to 65 μm*
			Cellular wall 442-1650 nm*
Al			Thickness of C wall 64.8±21.3 nm
			Precipitates† ~ 100 nm
			Size of precipitates† < 50 nm
			Nanoclusters << 50 nm
AlSi10Mg	Atomic density (atoms/m ³)	6.029 X 10 ²⁸	Kittle Kittle
	Mean acoustic velocity* (v) – (m/s)	3666	
	Debye Temperature* – (K)	155°C 428	
	Averaged phonon mean-free path ($3\lambda/Cvv$) – (Å)	80.0	
	Longitudinal sound velocity (m/s)	6453	
	Shear sound velocity (m/s)	3119	
Average acoustic velocity (v) (m/s)			3507
Debye temperature (K)			136°C 409
Thermal diffusivity (α_d) – (m ² /s)			4.648 X 10 ⁻⁶
Averaged phonon-mean-free Path from ($3\alpha_d/v$) – (Å)			39.8

- Nanoclusters, precipitates, and cellular structure significantly effect heat transfer at low temperature before cellular wall collapses.
- After the cellular wall collapses, the heat transfer will be only limited by electron and phonon mean free paths in the alloy.

Thermal diffusivity (α)



Thermal conductivity (λ)



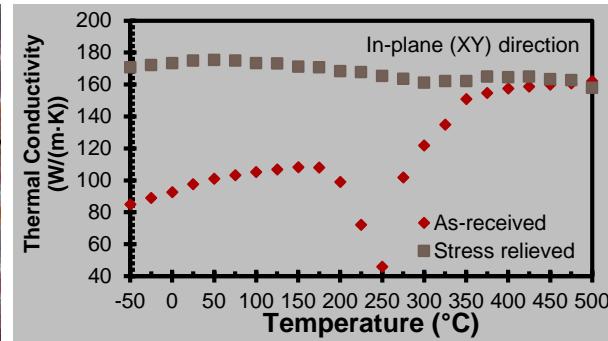
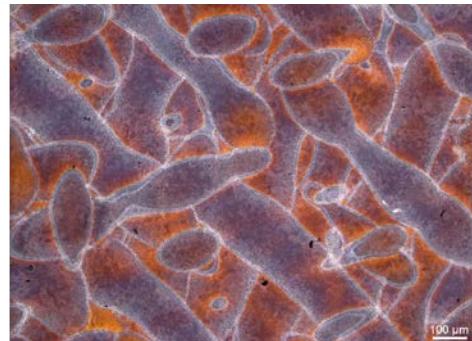
Conclusion

- Fast melting and rapid solidification can significantly impact the thermal properties of AM fabricated parts.
- Microstructure evolution, including the dissolution of excess Si, the growth of Si precipitates, and the collapsing of the cellular structure, has a profound effect on the thermal transport in AM fabricated AlSi10Mg alloy.
- Implications based on this study are important to ensure thermal performance of AM fabricated, solution treatable alloys for practical applications.

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Thank You



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Thermal calculation

(1) The mean free path of electron in pure aluminum can be calculated by

$$I_e = V_F \tau$$

Where I is the man free path, V_F is the velocity of the electron above Fermi level, and τ is the average time between electronic collisions. The Fermi velocity can be calculated by

$$V_F = \sqrt{2E_F / m_e}$$

Where the E_F is the Fermi energy and m_e is the effective mass of electron (9.11×10^{-31}). The Fermi energy at zero Kevin is given by

$$E_F = \frac{\hbar}{2m_e} \left(\frac{3N}{8\pi V} \right)$$

Where N/V is the free electron density, and \hbar is the Plank's constant. The average time between collision τ is determined by the mass of the electron, the number of atoms per unit volume, electrical resistivity (ρ), and the electron charge (e)

$$\tau = \frac{m_e}{\rho n e^2}$$

The thermal conductivity K can be estimated by the Wiedemann-Franz law

$$K = \frac{\sigma T}{3} \left(\frac{\pi k}{e} \right)^2$$

Where σ is the electrical conductivity and k is the Boltzmann constant.

(2) Phonon calculation

Phonon mean free path (l_p) above Debye temperature can be estimated by

$$l_p \approx \frac{3\lambda}{C_v v} = \frac{3\alpha}{v}$$

Where, C_v is the volumetric heat capacity, C_v is the volumetric heat capacity, v is the sound velocity in the medium, v_L measured longitudinal (v_L: 6453 m/s) and the shear (v_s: 3119 m/s) sound velocities by the following relationship,

$$v = \left[\frac{1}{3} \left(\frac{2}{v_s^3} + \frac{1}{v_L^3} \right) \right]^{-1/3}$$

(3) Debye temperature (θ_D)

$$\theta_D = \frac{\hbar v}{2k} \sqrt[3]{\frac{6N}{\pi V}}$$

Where k is the Boltzmann constant.

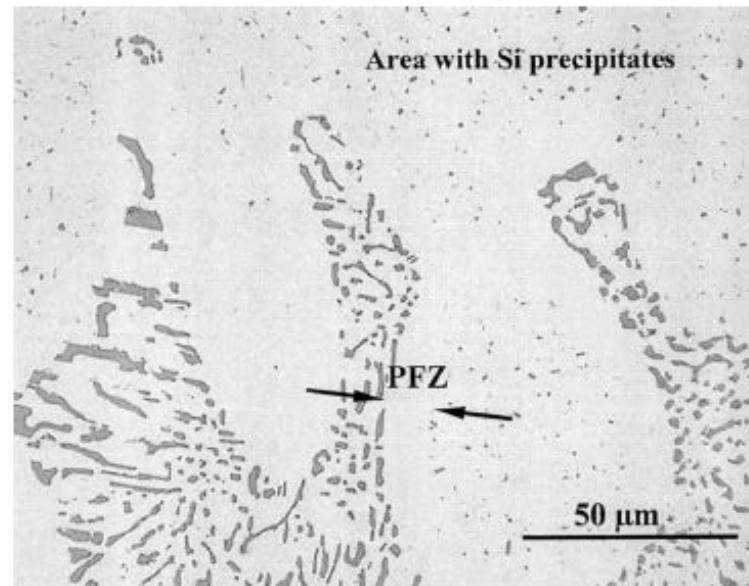


Fig. 9—Silicon precipitates within dendrites in AlSi7Mg0.2 alloy that has been extremely slowly cooled from 813 K.

L. Pedersen and L. Arnberg, “The effect of solution heat treatment and quenching rates on mechanical properties and microstructure in AlSiMg Foundry Alloys,” Metallurgical and Materials Transactions A **32A** 525-532 (2001)